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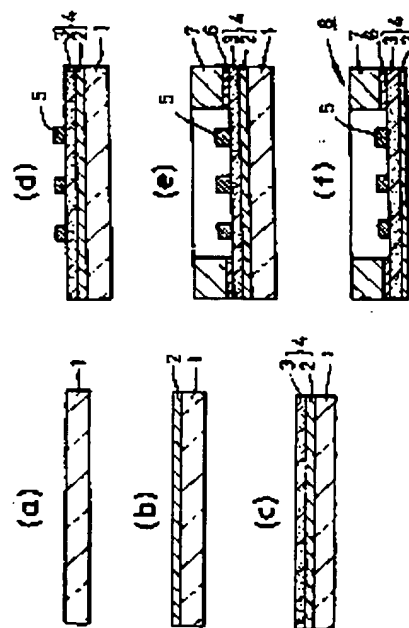
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(54) MASK FOR SOFT X-RAY TRANSFER AND ITS PRODUCTION

(57)Abstract:

PURPOSE: To obtain a titled mask which is strong to mechanical impact and has good flatness by constituting a support for a transfer pattern of a composite film of a polyimide film and a silicon dioxide film, and securing a support frame made of quartz glass on the silicon dioxide film.

CONSTITUTION: A polyimide film 2 and a silicon dioxide film 3 of about 0.2μ thickness are successively formed on a glass substrate 1 having about 100μ thickness and a smooth surface, thereby forming a support 4 consisting of a laminate of the films 2 and 3. A soft X-ray absorptive pattern 5 of about 0.2μ thickness consisting of Au, Pt, etc. is formed thereon. A support frame 7 made of quartz glass of about 250μ thickness subjected separately to prescribed windowing is adhered with an adhesive layer 6 on the film 3, whereafter the substrate 1 is removed from the film 2 and a mask 8 for soft X-ray transfer is obtd.



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